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DOCKET NO.: 278426US0PCT

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

GROUP: 3723

Mitsugu ABE, et al.

SERIAL NO: 10/549,294

ATTENTION:

FILING RECEIPT CORRECTIONS

FILED:

September 16, 2005

FOR:

MATERIAL FOR PURIFICATION OF SEMICONDUCTOR POLISHING

SLURRY, MODULE FOR PURIFICATION OF SEMICONDUCTOR

POLISHING SLURRY AND PROCESS FOR PRODUCING

SEMICONDUCTOR POLISHING SLURRY

REQUEST FOR CORRECTED OFFICIAL FILING RECEIPT

Office of Initial Patent Examination Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

The Patent Office is requested to provide a corrected Official Filing Receipt for the following.

PLEASE NOTE THAT THE 1ST 2ND 3RD AND 4TH APPLICANTS' CITIES ARE INCORRECT. THEY SHOULD READ AS FOLLOWS:

MITSUGU ABE, **ATSUGI-SHI**, JAPAN

NOBUYOSHI NAMBU, **YOKKAICHI-SHI**, JAPAN

OSAMU ITO, **YOKKAICHI-SHI**, JAPAN

MASAAKI OGITSU, TSUKUBA-SHI, JAPAN

KAZUO INOMATA, TOKYO, JAPAN

No fees are required. If you have any questions, please do not hesitate to contact us.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND, MAIER & NEUSTADT, P.C.

Norman F. Oblon

/ James H. Knebel Registration No. 22,630

Customer Number

22850

Tel. (703) 413-3000 Fax. (703) 413-2220 (OSMMN 03/06) Docket No: 278426US Serial No: 10/549,294



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IND CLMS **TOT CLMS FILING OR 371** DRAWINGS ATTY.DOCKET NO FIL FEE REC'D ART UNIT APPL NO. (c) DATE 6 278426US0PCT 1260 10/549,294 09/16/2005 3723

CONFIRMATION NO. 8085

22850 OBLON, SPIVAK, MCCLELLAND, MAIER & NEUSTADT, P.C. 1940 DUKE STREET ALEXANDRIA, VA 22314



Date Mailed: 06/05/2006

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please mail to the Commissioner for Patents P.O. Box 1450 Alexandria Va 22313-1450. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

App	lica	nt(s)
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Mitsugu Abe, Kanagawa, JAPAN; Atsug, Nobuyoshi Nambu, Mie, JAPAN; Osamu Ito, Mie, JAPAN; Masaaki Ogitsu, Ibaraki, JAPAN; Kazuo Inomata, Tokyo, JAPAN;

Assignment For Published Patent Application

Nomura Micro Science Co., Ltd., Atsugi-shi, Kanagawa, JAPAN

Power of Attorney: The patent practitioners associated with Customer Number 22850.

Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP04/03642 03/18/2004

Foreign Applications

JAPAN 2003-074581 03/18/2003

If Required, Foreign Filing License Granted: 06/04/2006

The country code and number of your priority application, to be used for filing abroad under the Paris Convention, is **US10/549,294**

Projected Publication Date: 09/14/2006

Non-Publication Request: No

RECEIVED:	0/09/06
RECEIVED:OBLON, SPIVAK,	McCLELLAND
MAIER & NEUSTA	
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nitials/Date Docketed:	KIK 6/04/06
Type of Resp(s):	
Due Date(s):	

Early Publication Request: No

Title

Material for purification of semiconductor polishing slurry, module for purification of semiconductor polishing slurry and process for producing semiconductor polishing slurry

Preliminary Class

451

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